

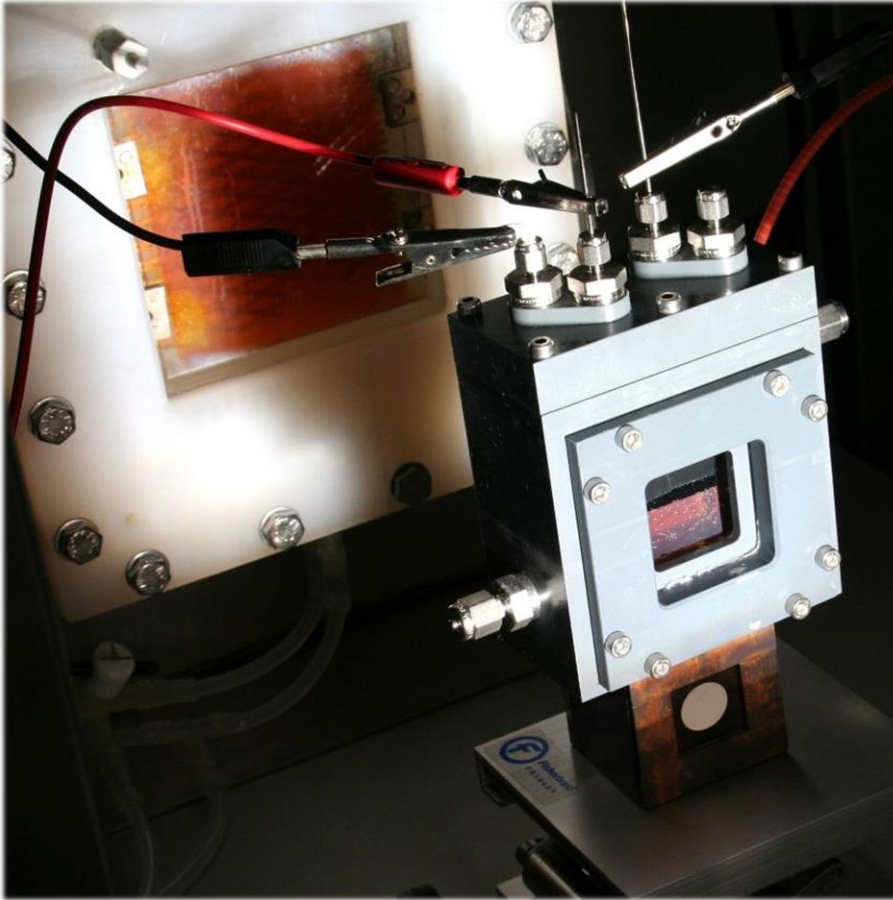


Evaluation of Hematite as a Photo-Anode

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Presentation Outline



1. Theory

2. Fabrication

3. Photo-response with and without Dopants

4. Hematite | Liquid Interfacial Structure

5. Future Research

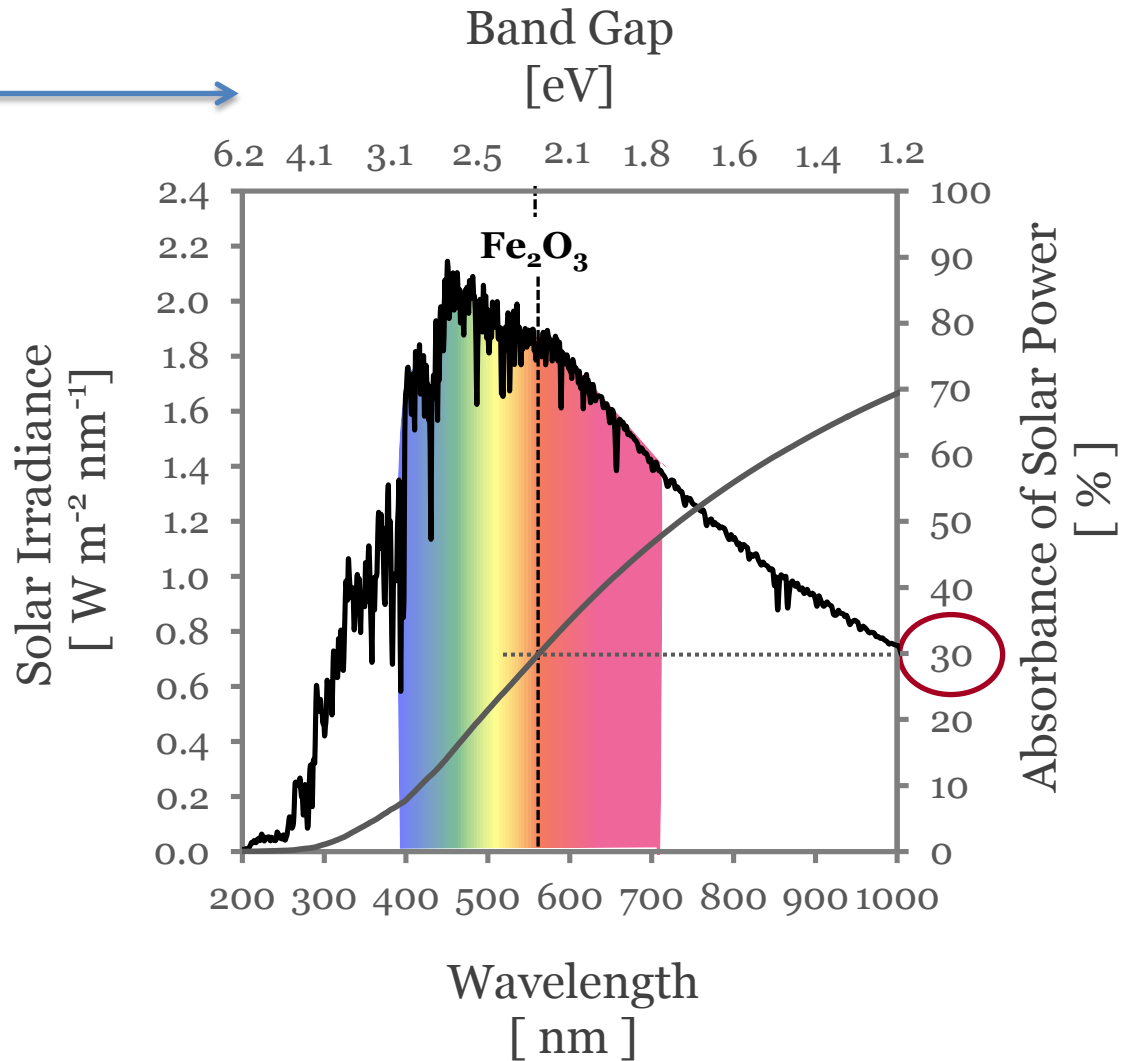
Pros and Cons of Hematite as a Photoanode

Suitability of Fe_2O_3 :

- ✓ Absorption spectrum well matched to solar spectrum
- ✓ Easily fabricated on a large scale at low cost
- ✓ Stable to decomposition by e^- and h^+ over wide potential range
- ✓ Valence band energy below that for decomposition of H_2O to O_2

Limitations of Fe_2O_3 :

- × Conduction band energy below decomposition potential for H_2O to H_2
- × Stable only in neutral / alkaline pH



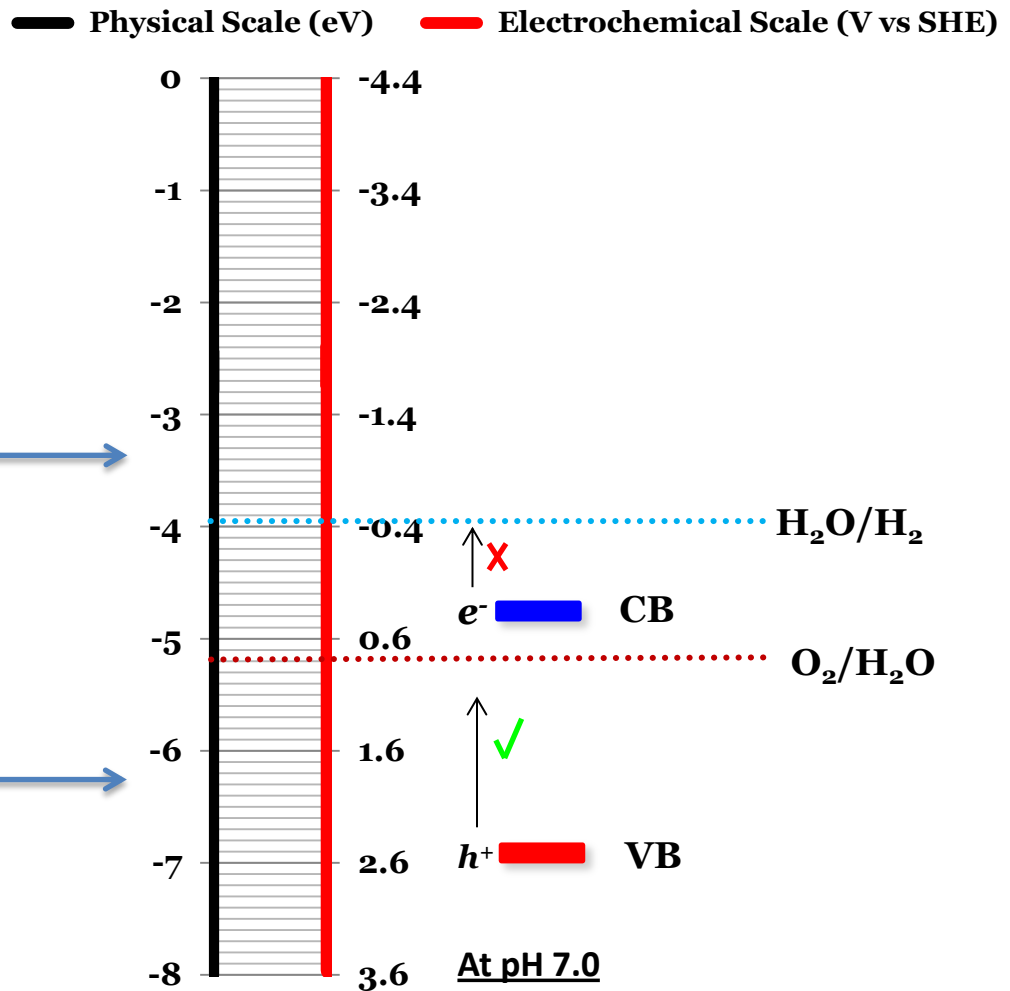
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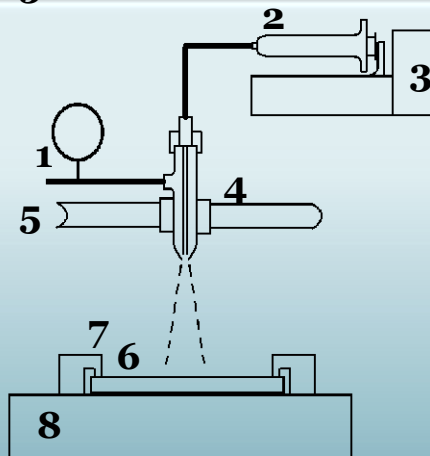
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Hematite Photoanode Production

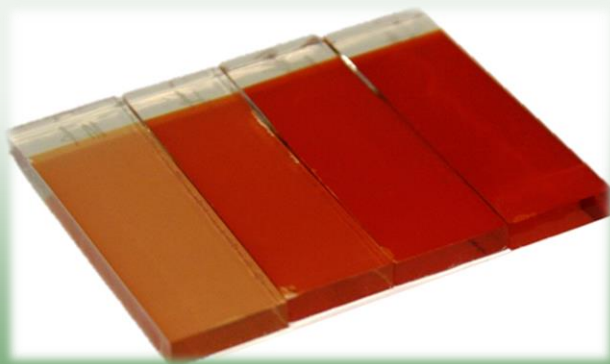
Fabrication of Fe_2O_3 and $\text{Sn}^{\text{IV}}\text{-Fe}_2\text{O}_3$ by Spray Pyrolysis

1. Compressed Air
2. Precursor reservoir
3. Syringe pump
4. Quartz nebuliser
5. CNC machine
6. Substrate
7. Clamping block
8. Hotplate

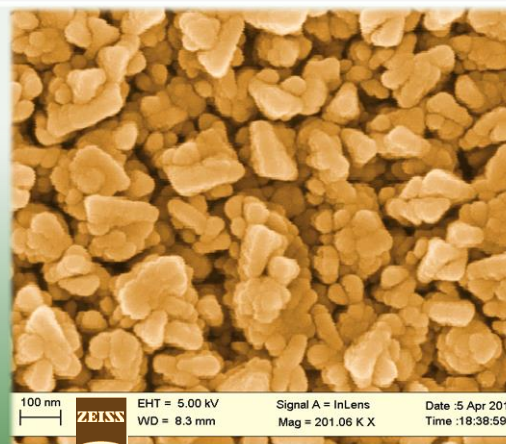


Fe_2O_3 coating produced by nebulising $\text{Fe}^{\text{III}}\text{Cl}_3$ and $\text{Sn}^{\text{IV}}\text{Cl}_4$ in solvent onto heated FTO glass

The Electrode



Photographic image

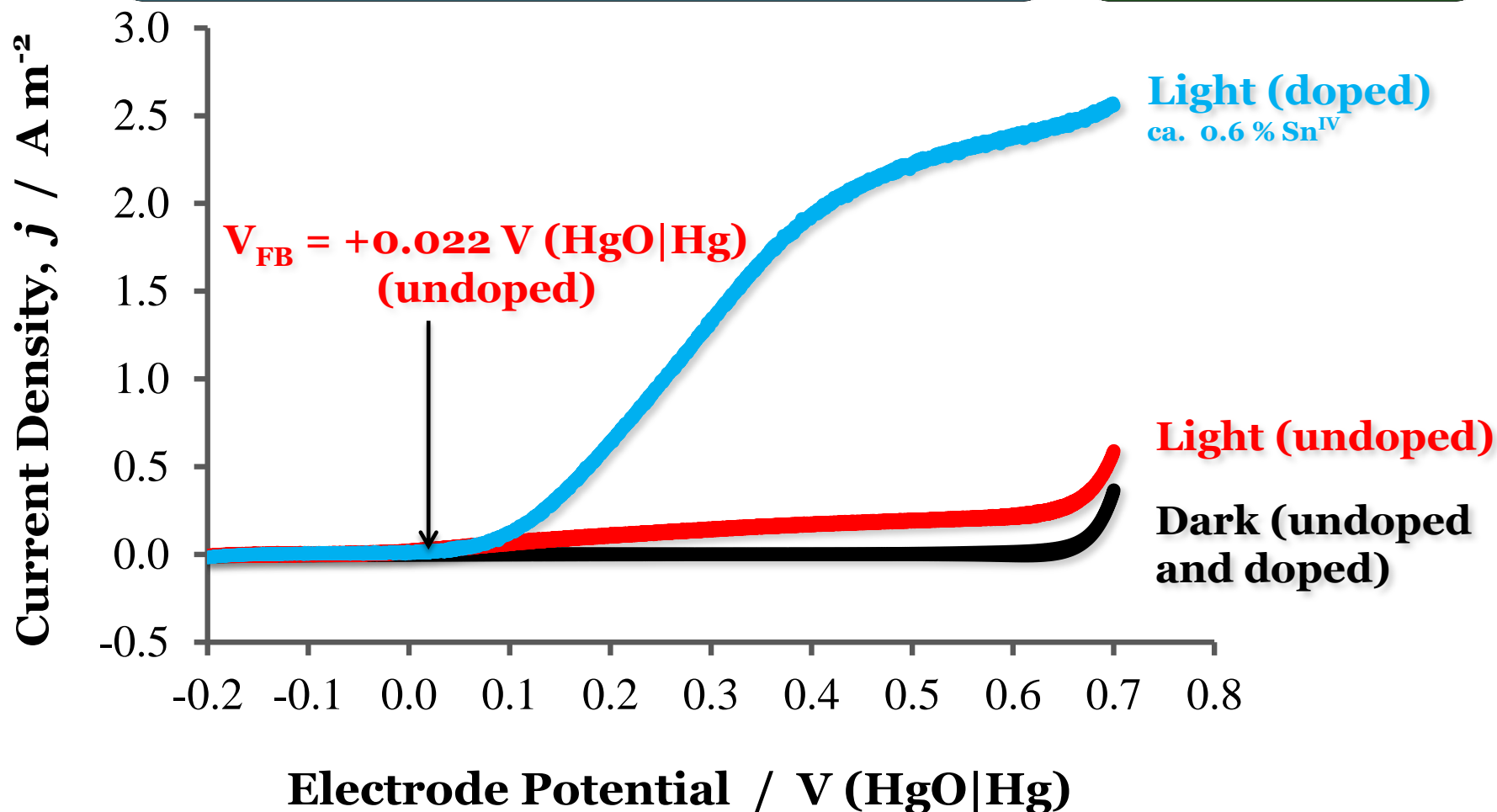


SEM image

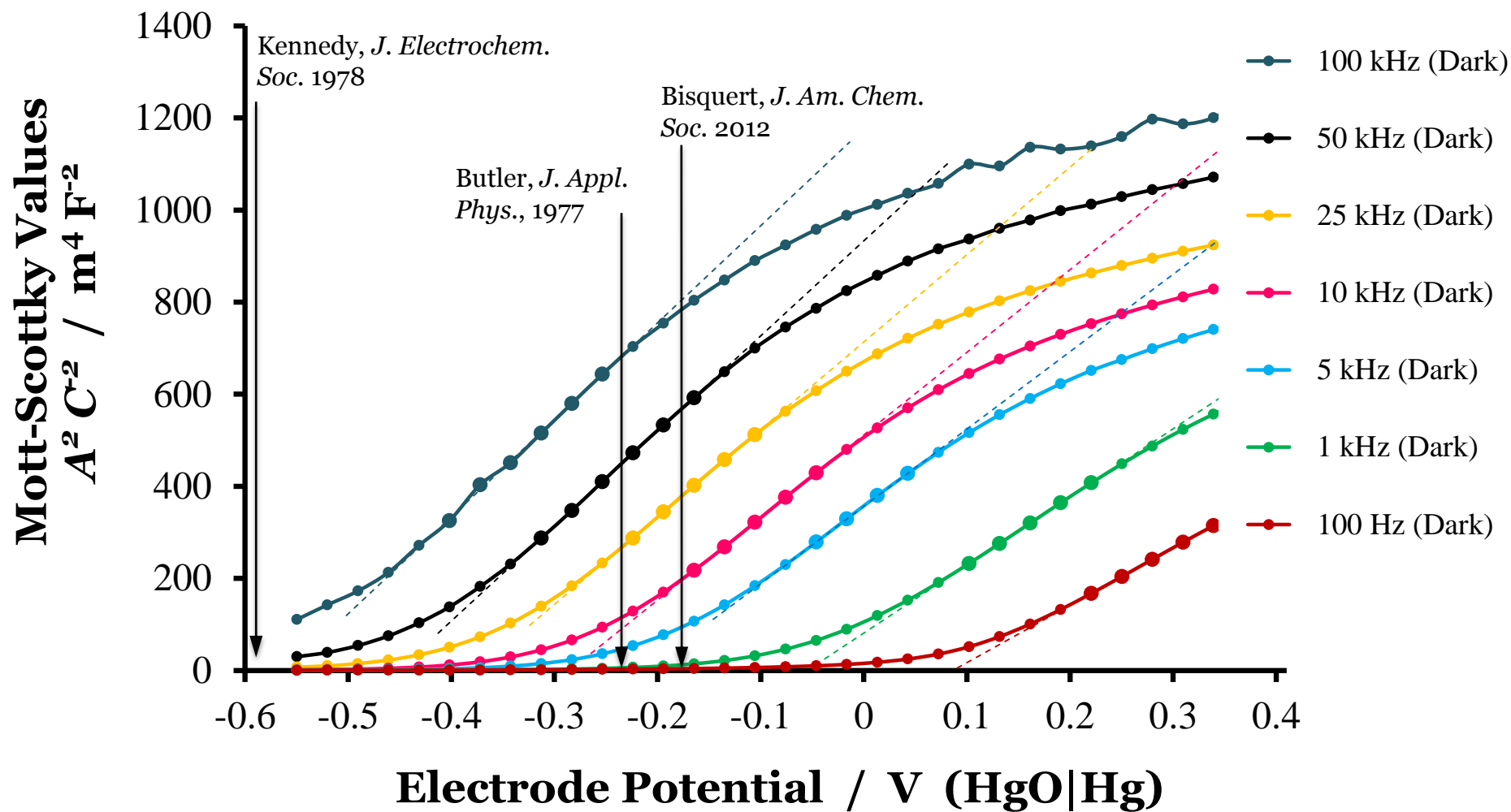
Hematite Photo-Response in Steady State

Effect of Potential (applied at 1 mV s^{-1}) and White Light
Illumination (49 W m^{-2} Xe) on
ca. 40 nm thick films on FTO | 1 M NaOH (pH 13.7)

Illuminated area
 $\approx 0.15\text{ cm}^2$



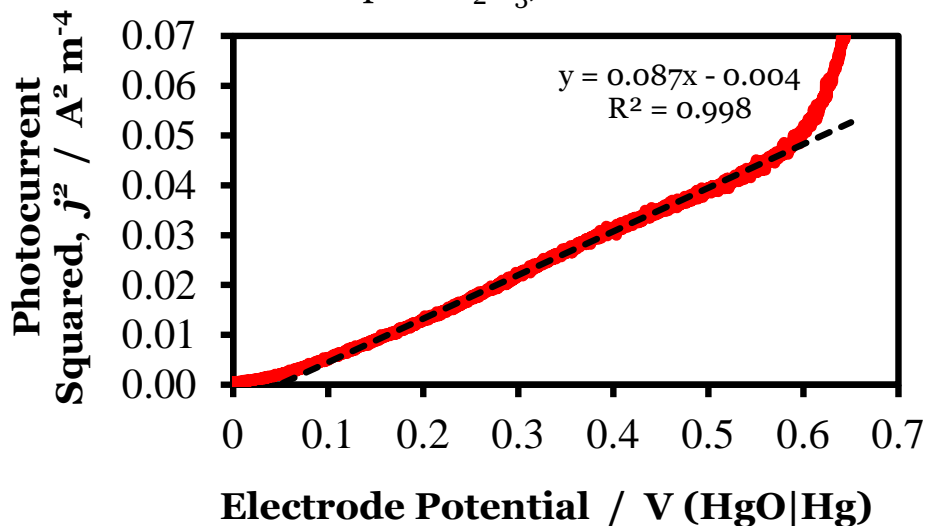
Flat Band and Charge Carrier Determination



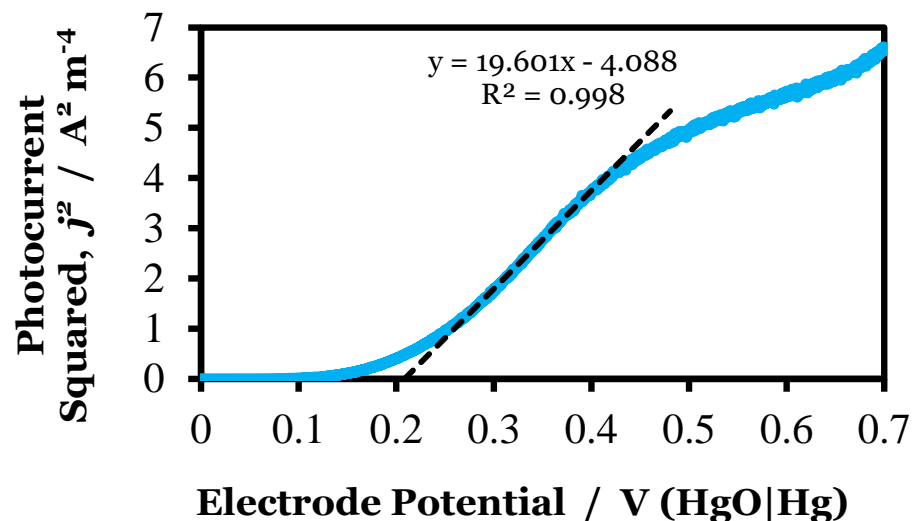
$$V_{FB} = V_{x\text{-intercept}} - \frac{k_B T}{e_0}$$

Evaluation of the Flat Band Potential from j_2 vs V

Undoped Fe_2O_3 , scan rate = 1 mV s^{-1}



Sn^{IV} doped Fe_2O_3 , scan rate = 1 mV s^{-1}



$$V_{FB} = V_{\text{x-intercept}}$$

Material	V_{FB} (HgO Hg) / V	<i>pH of zero charge</i>
Undoped Fe_2O_3	+0.02	6.7 *
Sn^{IV} doped Fe_2O_3	+0.18	< 6.7 (?)

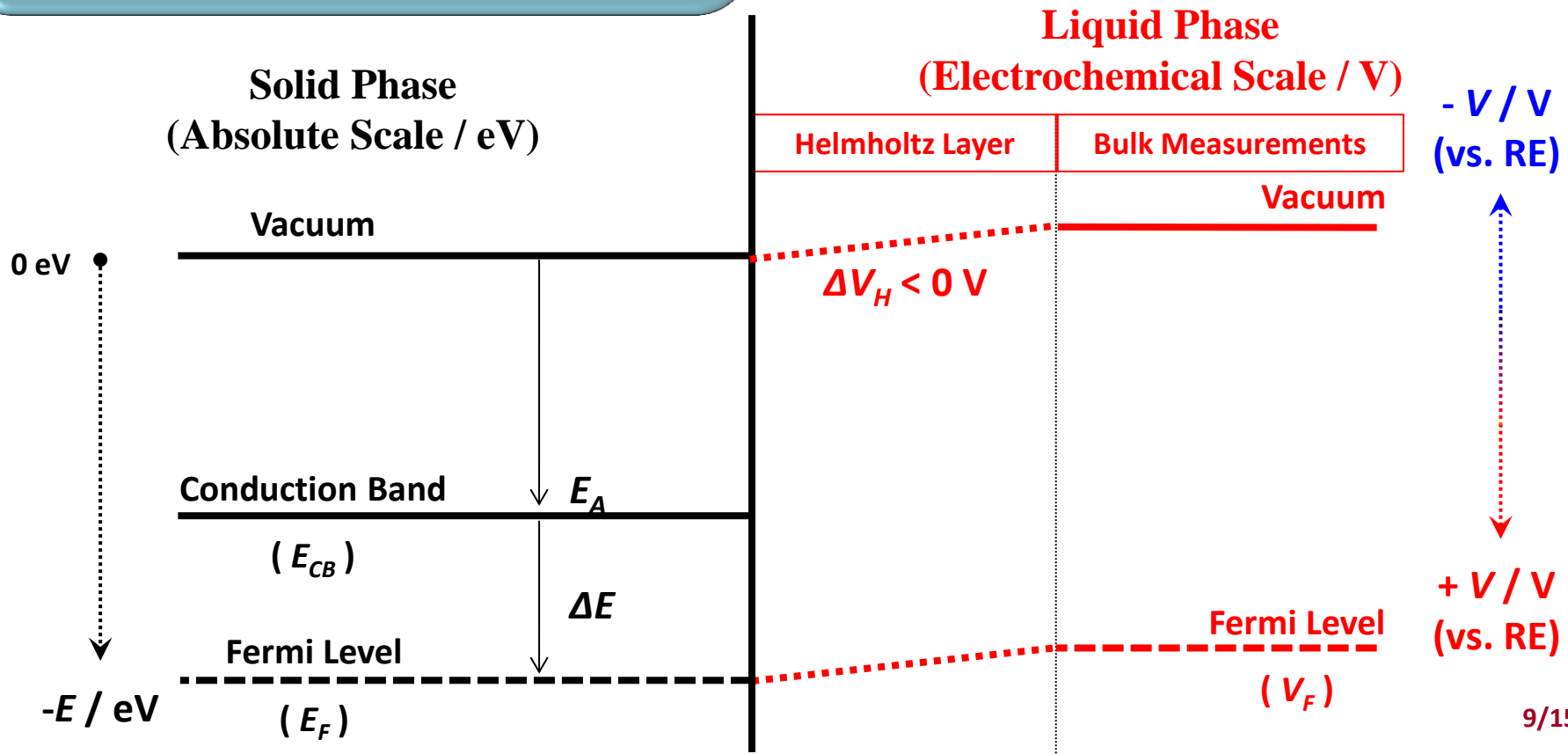
Verification of the Solid|Liquid Energetic Alignment

$$\Delta V_H = \frac{2.3RT}{F} \left[\{pH(pzc) - pH\} - \log \left\{ \frac{[Fe-O^-]}{[Fe-OH_2^+]}} \right\}^{\frac{1}{2}} \right]$$

For Fe_2O_3 in alkaline solution

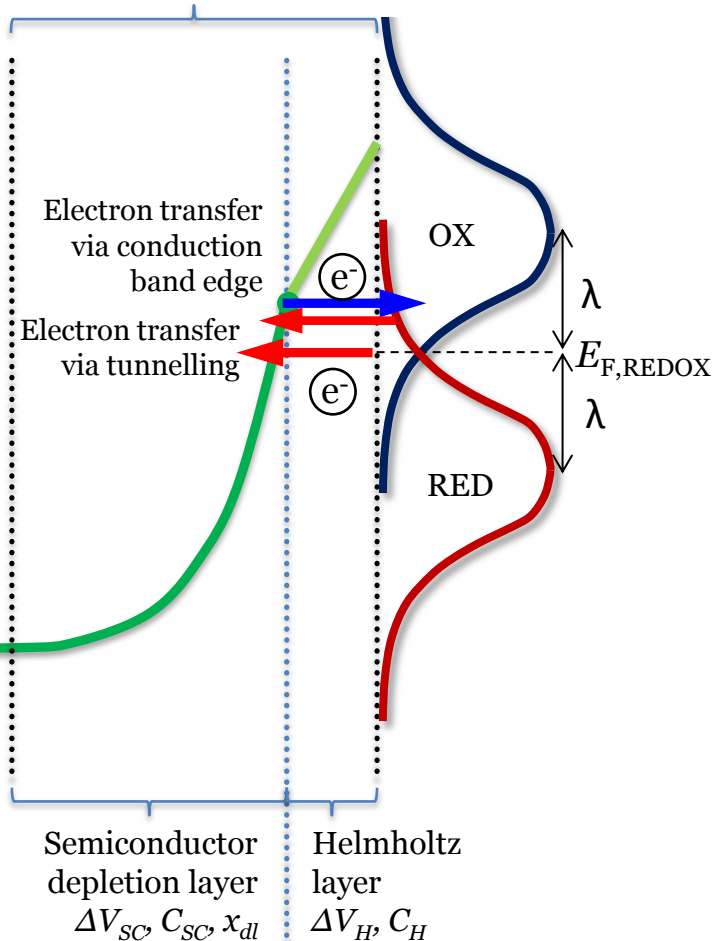
$$pH \gg pH(pzc) \text{ and } \frac{[Fe-O^-]}{[Fe-OH_2^+]} \gg 1$$

$$E_A + \Delta E = -(V_{F \text{ (measured)}} - V_H + 4.44 + E^0(\text{RE vs SHE}))$$



Modelling the Hematite | Liquid Interface

Semiconductor | Liquid Interfacial Region



Constructing an Interfacial Model

- Distribution of applied bias

$$\Delta V_{Interface} = \Delta V_{SC} + \Delta V_H$$

- Potential drop across the Helmholtz layer

$$\Delta V_H = \Delta V_{H,0} + \frac{Q_{SC}}{C_H}$$

- Electric charge in semiconductor depletion layer

$$Q_{SC} = (2\epsilon_r \epsilon_0 N_D)^{\frac{1}{2}} \left(\Delta E_{SC} - \frac{k_B T}{e_0} \right)^{\frac{1}{2}}$$

- Total interfacial capacitance

$$\frac{1}{C_{Interface}} = \frac{1}{C_{SC}} + \frac{1}{C_H}$$

- Semiconductor capacitance

$$C_{SC} = \left(\frac{2}{\epsilon_0 \epsilon_r e_0 N_D} \left(V_{F,SC} - V_{FB} - \frac{k_B T}{e_0} \right) \right)^{\frac{1}{2}}$$

- Depletion layer thickness

$$x_{dl} = 2L_D \left(\frac{\epsilon_0 \Delta V_{SC}}{k_B T} - 1 \right)^{0.5}$$

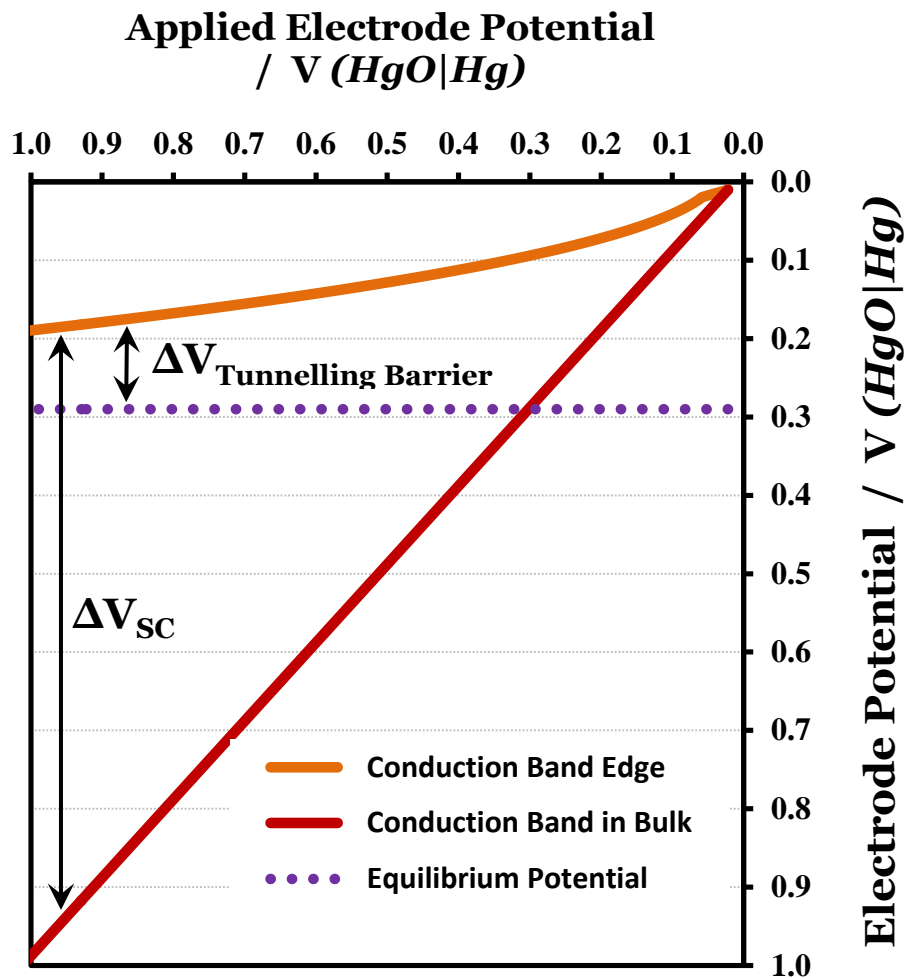
- Tunnelling distance and probability

$$x_{tunnelling} = 2 \left(\frac{\epsilon \epsilon_0}{2e_0 n_{CB}} \right)^{\frac{1}{2}} \left[\left(E_{CB}^{Bulk} - E_{CB}^{Surface} \right)^{\frac{1}{2}} - \left(E_{CB}^{Bulk} - E_{rev, O_2/H_2O} \right)^{\frac{1}{2}} \right] + x_{dl}$$

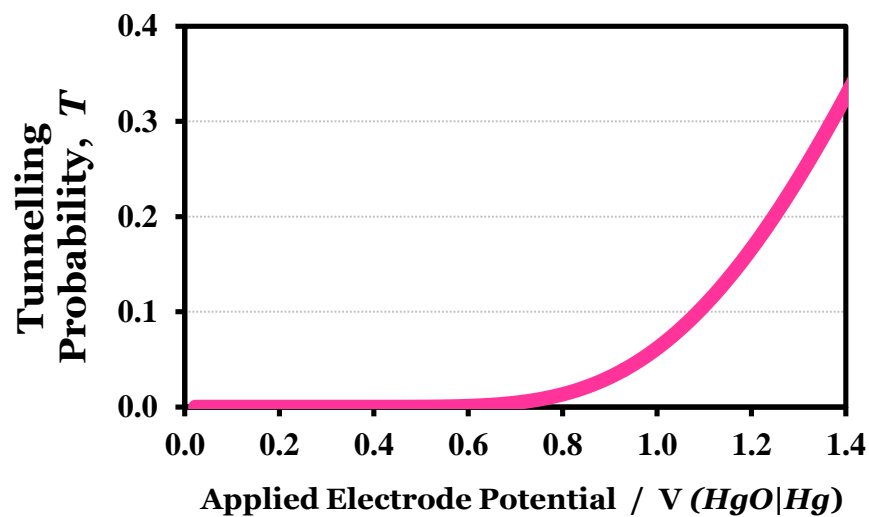
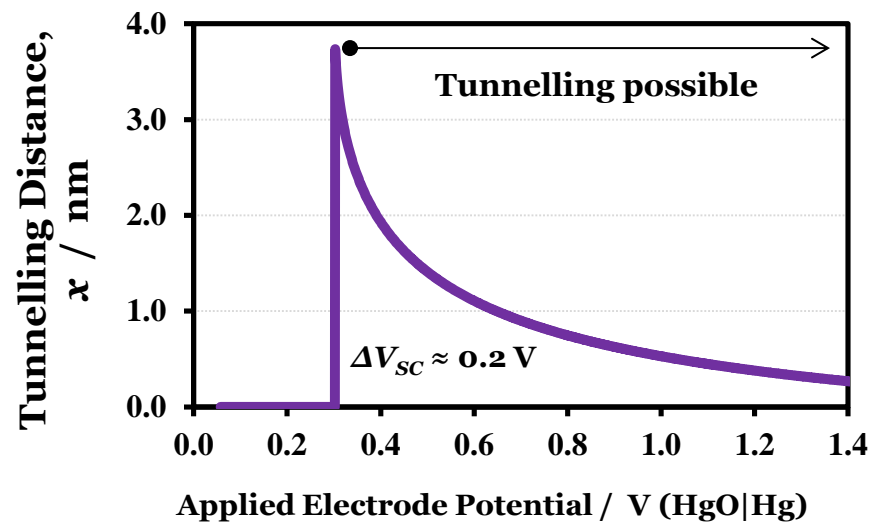
$$T(e_0 \phi_{CB}, E_D) = \exp \left[-K \left(\sqrt{e_0 \phi_{CB} \times E_D} - (e_0 \phi_{CB} - E_D) \ln \left\{ \frac{\sqrt{e_0 \phi_{CB}} - \sqrt{E_D}}{\sqrt{e_0 \phi_{CB}} - E_D} \right\} \right) \right]$$

$$K = \frac{4\pi e_0}{h} \sqrt{\frac{4m_e^* \epsilon_0 \epsilon_r}{N_D e_0^2}} \quad ; \quad E_D = E_{CB}^{Surface} - E_{REDOX}$$

Model Predictions for Interfacial Behaviour



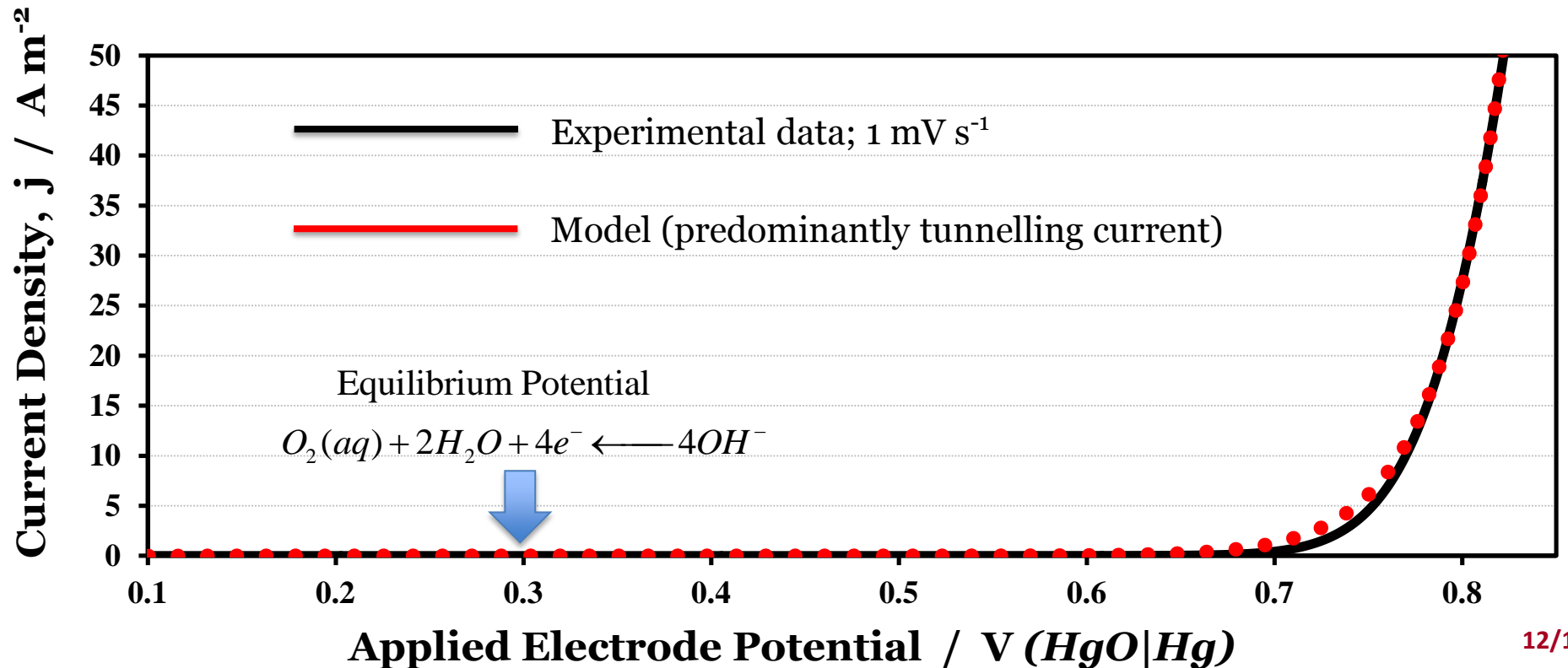
$$\Delta V_{\text{Tunnelling}} = V_{\text{Rev}} - V_{\text{CB}}^{\text{Surface}}$$



Interfacial Charge Transfer Prediction

j_{Total} = Anodic & Cathodic currents through CB edge + Anodic tunnelling current into CB

$$j = \frac{j_{T,0} \exp\left\{\frac{\alpha F}{RT}(E_F - E_{\text{redox}})\right\} T(x(E_F)) + C(OH^-) N_{CB} \left(\frac{k_B T}{\lambda \pi}\right)^{\frac{1}{2}} \exp\left\{-\frac{e_0^2(E_{CB}^{\text{Edge}} - E_{\text{redox}} + \lambda)^2}{2\lambda k_B T}\right\}}{1 + \frac{j_{T,0} \exp\left\{\frac{\alpha F}{RT}(E_F - E_{\text{redox}})\right\} T(E_F) + C(OH^-) N_{CB} \left(\frac{k_B T}{\lambda \pi}\right)^{\frac{1}{2}} \exp\left\{-\frac{e_0^2(E_{CB}^{\text{Edge}} - E_{\text{redox}} + \lambda)^2}{2\lambda k_B T}\right\}}{4Fk_{m,OH^-}[OH^-]}} - \frac{C(O_2(aq)) N_{CB} \exp\left\{-\frac{e_0}{k_B T}(E_{CB}^{\text{Edge}} - E_F)\right\} \left(\frac{k_B T}{\lambda \pi}\right)^{\frac{1}{2}} \exp\left\{-\frac{e_0^2(E_{CB}^{\text{Edge}} - E_{\text{redox}} - \lambda)^2}{2\lambda k_B T}\right\} \exp\left\{\frac{(1-\alpha)F}{RT}(E_F - E_{\text{redox}})\right\}}{1 + \frac{C(O_2(aq)) N_{CB} \exp\left\{-\frac{e_0}{k_B T}(E_{CB}^{\text{Edge}} - E_F)\right\} \left(\frac{k_B T}{\lambda \pi}\right)^{\frac{1}{2}} \exp\left\{-\frac{e_0^2(E_{CB}^{\text{Edge}} - E_{\text{redox}} - \lambda)^2}{2\lambda k_B T}\right\} \exp\left\{\frac{(1-\alpha)F}{RT}(E_F - E_{\text{redox}})\right\}}{4Fk_{m,O_2}[O_2(aq)]}}$$

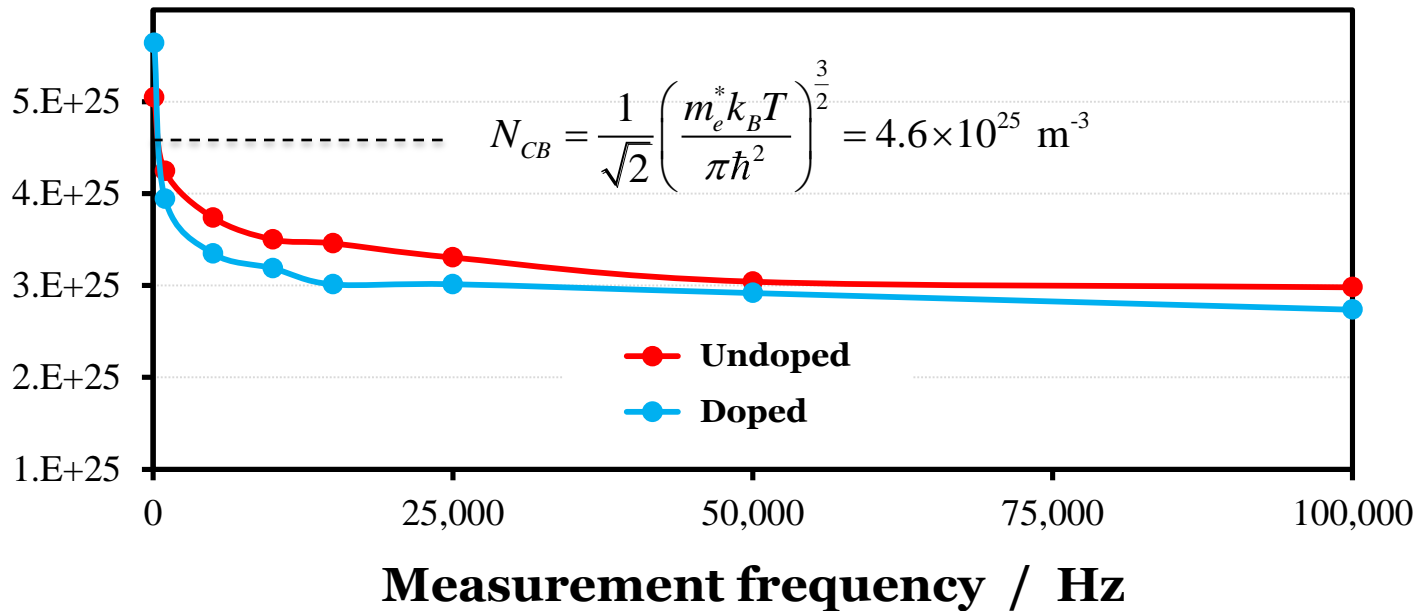


Frequency Dependence of Charge Carrier Concentration

The charge carrier densities are calculated from the slopes of Mott-Schottky plots, obtained at higher frequencies

$$N_D = \frac{2}{\epsilon_0 \epsilon_r e_0} \frac{d(C^2 A^{-2})}{dV}$$

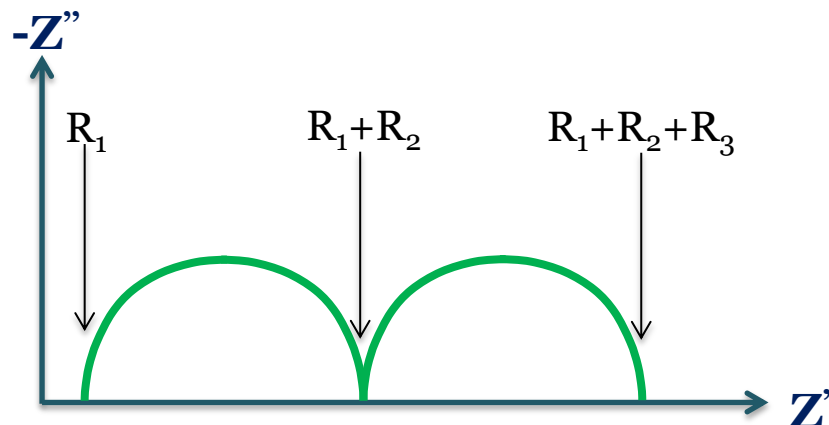
Charge Carrier
Concentration
 N_D / m^{-3}



Material	N_D / m^{-3}
Undoped Fe_2O_3	2.80×10^{25}
Sn^{IV} doped Fe_2O_3	2.75×10^{25}

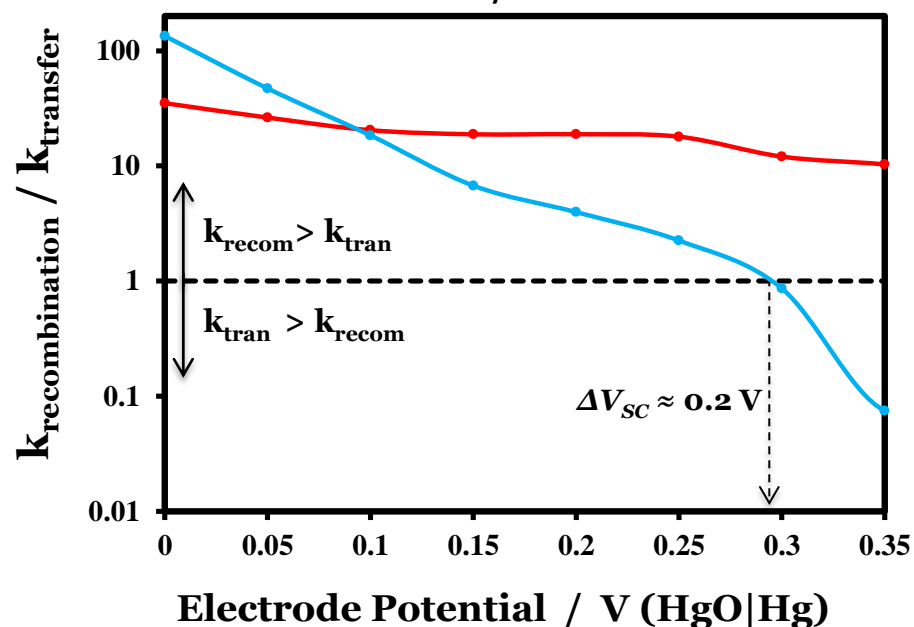
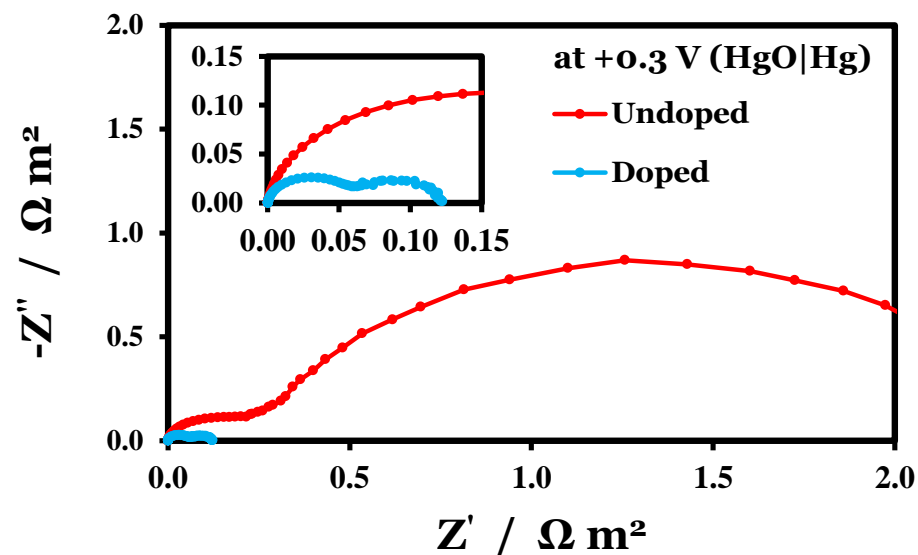
Effect of Dopant of Recombination Kinetics

Analysis of typical Nyquist plots obtained under illumination



$$\frac{k_{\text{recombination}}}{k_{\text{transfer}}} = \frac{(R_3 - R_1)}{(R_2 - R_1)} - 1$$

K.G. Upul Wijayantha, S. Saremi-Yarahmadi and L.M. Peter, *Phys. Chem. Chem. Phys.* **13**, 2011, 5264



Conclusions

- We have obtained a reasonably good understanding of interfacial behaviour of undoped Fe_2O_3 films in steady state
 - ❑ Photocurrent onset potential cannot be shifted further left as limited by flat band potential, obtained from j^2 vs. V plots
 - ❑ To maximise the photocurrent, surface area should be increased and recombination rate minimised
- The influence of dopants must be better understood, particularly their effect on recombination rate
- The pH of zero charge must be experimentally determined for each film in order to improve model accuracy

END

Interfacial Characteristics of the Undoped Fe₂O₃

$$E_A + (E_{CB} - E_F) = - (V_{F \text{ (measured)}} - \Delta V_H + 4.44 + E^0(RE \text{ vs SHE}))$$

<u>Quantity</u>	<u>Value</u>	<u>Unit</u>	<u>Reference</u>
<u>On the absolute scale</u>			
E_A	-4.72	eV	Butler M.A., Ginley D.S., Eibschutz M. (1977) <i>J. Appl. Phys.</i> 48, 3070
ΔE	-0.013	eV	Calculated using the charge carrier density, n_{CB} , obtained from Mott-Schottky plots
<u>On the electrochemical scale</u>			
$V_{FB} \text{ (measured)}$	+ 0.022	V (HgO Hg)	Determined from the intercept of $(j_{\text{photocurrent}})^2$ with the x-axis
ΔV_H	-0.15	V	Calculated as the only unknown in the energy-potential balance
$[Fe-O^-] / [Fe-OH_2^+] \text{ (at surface)}$	8.38×10^8	1	
<u>For the conversion between the two scales</u>			
$E^0(RE) = E^0(HgO Hg)$	+0.12	V (SHE)	Experimentally measured
$E^0(SHE)$	0	V (SHE)	Standard value

Electrochemical Impedance of Hematite in the Dark

Circuit representation of the interfacial charge transfer

